Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1334	(702/94,150).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/09/08 09:24
L2	0	(photolithograph\$3 and (artifact mark) and (stage table) and (wafer substrate) and measur\$3 and distance and grid and (magnification rotation) and field).clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/08 09:25
L3	5	(photolithograph\$3 and (artifact mark) and (stage table) and (wafer substrate) and measur\$3 and distance).clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/08 09:25
S1	2057	(702/94-95,87,56-59).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/01/04 14:54
S3	2813	((702/94-95,87,150-151) or (700/279,56-59)).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/19 12:49
S4	2674	S3 and @ad < "20040902"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/19 12:49
S5	203868	calibration	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/19 12:50
S6	970716	alignment	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/19 12:50

S7	663361	grid or coordinate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT;	OR	ON	2005/08/19 12:50
58	5665280	reference marker artifact	IBM_TDB US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/19 12:50
59	96674	wafer and fabrication	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/19 12:50
S10	523	S4 and S6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/19 12:51
S11	38	S10 and S9	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/19 12:54
S12	20127	S6 and S8 and S9 and @ad < "20040902"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/19 12:55
S13	1015	S12 and S7 and S5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/19 12:56
S14	678	S13 and perpendicular	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/19 12:56

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S15	8	S14 and (field near grid)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/19 12:57
S16	669	S14 and field	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/19 12:57
S17	412	S16 and offset	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/19 12:58
S18	383	S17 and structure	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/19 12:58
S19	6	S18 and (known adj distance)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/19 12:59
S20	332	S18 and parameter	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/19 12:59
S21	296	S20 and pair	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/19 13:00
S22	214	S21 and axis	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/19 13:00

S23	205	S22 and (move or moving or moved)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/19 13:01
S24	201	S23 and location	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/19 13:02
S25	11	(("6557163") or ("6528219") or ("6498352") or ("6436595") or ("5763894")).PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/08/22 16:40
S26	948	wafer and fabrication and (artifact marker) and stage	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/01/04 16:36
S27	301	S26 and (photlithography lithography) and (outisde off "away from")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/01/04 16:37
S28	261	S27 and @ad < "20040902"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/01/04 16:46
S29	47	wafer and fabrication and (stage same (artifact))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/01/04 16:47
S30	40	S29 and @ad < "20040902"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/01/04 16:47

S31	1997	(430/22).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/01/05 13:42
S32	1671	S31 and @ad < "20040902"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/01/05 13:42
S33	4	S32 and artifact and stage	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/01/05 13:43
S34	130	S32 and grid	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/01/05 13:44
S35	41	S34 and magnification and rotation\$2	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/01/05 13:44
S36	4	(("6847432") or ("6532056") or ("6700667") or ("6498352")).PN.	USPAT	OR	OFF	2006/01/23 07:53
S37	2	(("6906780") or ("5976737")).PN.	USPAT; IBM_TDB	OR	OFF	2006/09/07 09:06
538	9086	((355/53,55) or (430/311)).CCLS.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/09/07 09:07
S39	6568	S38 and (wafer substrate) and (mark\$2 artifact reference)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/07 09:17

S40	549	S39 and ((grid field) near4 (parameters alignm\$4 magnification rotation\$3 coordinat\$2))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/07 09:15
S41	516	S40 and (determin\$3 measur\$3 obtain\$2 calculat\$3) and (distance offset spac\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/07 09:16
S42	443	S41 and (lithograph\$4 photolithograph\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/07 09:16
S43	212	S42 and ((mark\$2 artifact reference) near4 (stage tray table))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/07 09:22
S44	75	S43 and calibrat\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/09/07 09:23